



DOCKET NO.: 264681US0XPCT

IFW

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

IN RE APPLICATION OF:

Kai SCHUMACHER, et al.

SERIAL NO: 10/524,037

GROUP: 1762

FILED: February 9, 2005

EXAMINER:

FOR: SILICON DIOXIDE DISPERSION

LETTER

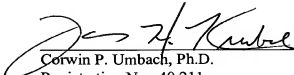
Mail Stop DD
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

On July 13, 2006, we filed an Information Disclosure Statement citing reference entitled "Principles and Applications of a Silica Produced by Flame Hydrolysis", by R. Bode, et al. Submitted herewith is the English Translation of the reference for the Examiner's consideration.

Respectfully Submitted,

OBLON, SPIVAK, McCLELLAND,
MAIER & NEUSTADT, P.C.
Norman F. Oblon


Corwin P. Umbach, Ph.D.
Registration No. 40,211

Customer Number

22850

Tel. (703) 413-3000
Fax. (703) 413-2220
(OSMMN 03/06)

James H. Knebel
Registration No. 22,630

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PATENT AND TRADEMARK OFFICE

ATTY DOCKET NO.

SERIAL NO.

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10/524,037

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FILING DATE

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LIST OF REFERENCES CITED BY APPLICANT



U.S. PATENT DOCUMENTS

EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE
	AA					
	AB					
	AC					
	AD					
	AE					
	AF					
	AG					
	AH					
	AI					
	AJ					
	AK					
	AL					
	AM					
	AN					

FOREIGN PATENT DOCUMENTS

	DOCUMENT NUMBER	DATE	COUNTRY	TRANSLATION	
				YES	NO
	AO				
	AR				
	AD				
	AR				
	AS				
	AT				
	AU				
	AV				

OTHER REFERENCES (Including Author, Title, Date, Pertinent Pages, etc.)

/D.L./	AW	R. BODE, et al., Principles and Applications of a Silica Produced by Flame Hydrolysis, pages 1-28 (submitting English translation only)
	AX	
	AY	
	AZ	

☐ Additional References sheet(s) attached

Examiner /Diana Liao/

Date Considered 09/29/2008

*Examiner: Initial if reference is considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.